II. Response to Claim Rejection - 35 U.S.C. § 102(e)

Claims 1-23 are rejected under 35 U.S.C. § 102(e) as allegedly being anticipated by Kawamura et al.

Applicants respectfully traverse the rejection and submit that Kawamura et al does not disclose, teach or suggest the present invention.

The Examiner relies on an embodiment of the Kawamura et al in which patterned graft polymerization is conducted, which is different from the present invention. Specifically, the process of Kawamura et al does not include imagewise forming a region having an ability to initiate polymerization. In Kawamura et al, polymerization initiating ability is provided on the entire surface, thus not meeting the element of forming a pattern as recited in the present claims. Due to this difference, patterned exposure is conducted in the process of the cited reference whereas the entire surface is exposed to light in the presently claimed invention. As a result, the definition of the pattern obtained is affected by the difference. For at least these reasons, the present claims are not anticipated by Kawamura et al.

Further, in the process of Kawamura et al, mask exposure is conducted. In general, rays are not completely parallel in the exposure process, especially in the case of inexpensive exposure apparatuses. Therefore, when patterned exposure is conducted, the pattern obtained is blurred by diffraction or the like depending on the distance between the mask and the graft face. In contrast, a mask is not used for graft polymerization in the presently claimed process, and the entire surface is exposed, whereby the above problem accompanying the process of the cited reference does not occur in the presently claimed invention.

Moreover, the process of the present invention is applicable to non-flat surfaces while the process of Kawamura et al is not generally applicable to non-flat surfaces. This is because the process of Kawamura et al involves mask exposure for graft polymerization.

In view of the above, the process of the presently claimed invention is clearly different from the process of Kawamura et al and has the above advantages over the process of Kawamura et al. Thus, the present claimed process is neither anticipated nor rendered obvious by Kawamura et al.

The presently claimed invention and Kawamura et al are also different in the patterned material that is obtained. Since the polymerization initiator is provided on the entire surface in the process of Kawamura et al, the polymerization initiator <u>remains</u> in the unexposed region (non-graft region) after exposure. The remaining polymerization initiator adversely affects the pattern with the passage of time, for example, causing film coloration. In contrast, the polymerization initiator is provided imagewise in the present invention, whereby the polymerization initiator is not present in the non-graft region. Accordingly, the patterned material of the presently claimed invention is <u>structurally</u> different from the patterned material of Kawamura et al and has improved characteristics. Thus, Kawamura et al does not anticipate the present invention nor render obvious the present invention.

Accordingly, Applicants respectfully request withdrawal of the rejection under 35 U.S.C. § 102.

III. Conclusion

In view of the above, reconsideration and allowance of this application are now believed to be in order, and such actions are hereby solicited. If any points remain in issue which the

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Response under 37 C.F.R. § 1.111 U.S. App. Ser. No. 10/735,769

Examiner feels may be best resolved through a personal or telephone interview, the Examiner is kindly requested to contact the undersigned at the telephone number listed below.

The USPTO is directed and authorized to charge all required fees, except for the Issue Fee and the Publication Fee, to Deposit Account No. 19-4880. Please also credit any overpayments to said Deposit Account.

Respectfully submitted,

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